

Metal oxides 3-D arrays by aqueous chemical growth

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A novel concept based on a general thermodynamic model of nucleation and growth monitoring by chemical and electrostatic control of the water-oxide interfacial tension and an aqueous thin film processing technique has been developed to fabricate very large 3-D arrays of crystalline metal oxides onto various substrates at mild temperatures¹. The goal is to design at low-cost a new generation of functional *purpose-built* metal oxide materials at nano-, meso- and micro-scale with controlled particle size, morphology and orientation (fig.1). Such well-designed materials should lead to a better fundamental understanding of their electronic structure² and physical/chemical properties as well as to develop novel and optimized devices³.

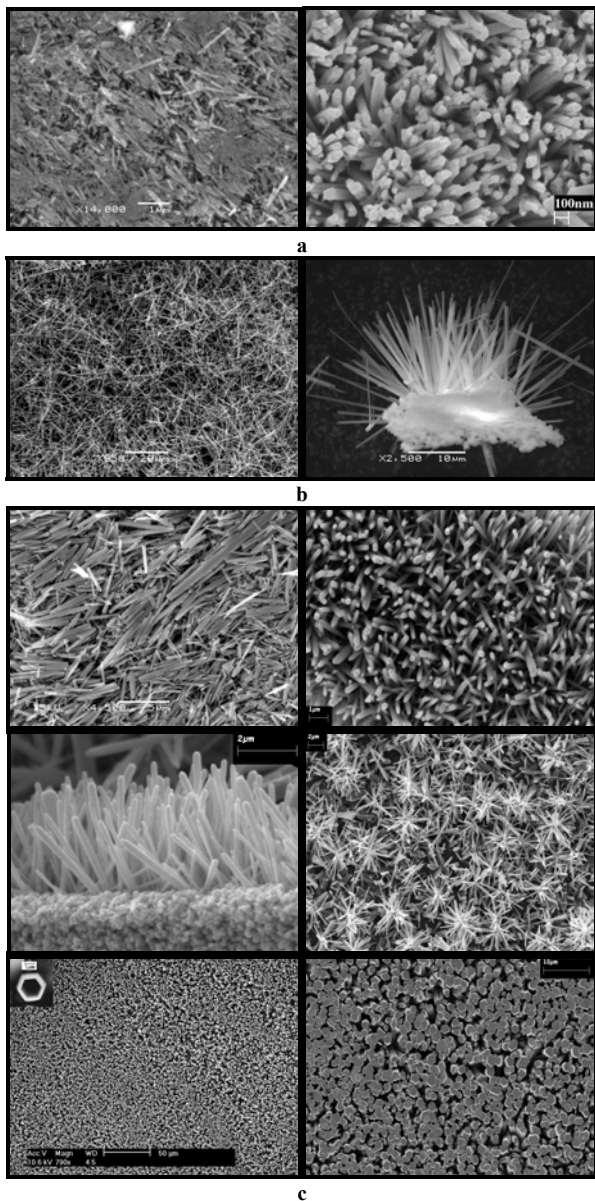


Fig. 1) SEM micrographs of 3-D arrays of some transition metal oxides (α -Fe₂O₃ (a); γ -MnOOH (b); ZnO (c)) consisting of anisotropic crystallites grown by aqueous chemical growth onto various substrates.

Patterning, assembly and integration of 1-D nanomaterials as functional 3-D network is an important challenge scientists have to face to develop future practical nanodevices. Non-lithographic fabrication of large patterned 3-D arrays at low-cost is achievable with the aqueous chemical growth technique and figure 2 shows various examples of such ability on crystalline ZnO nanomaterials. Well-defined stars and stripes of ZnO nanorods of various patterns are obtained by chemical and/or physical activation of the silicon wafer substrates. Further investigations are currently under scrutiny.

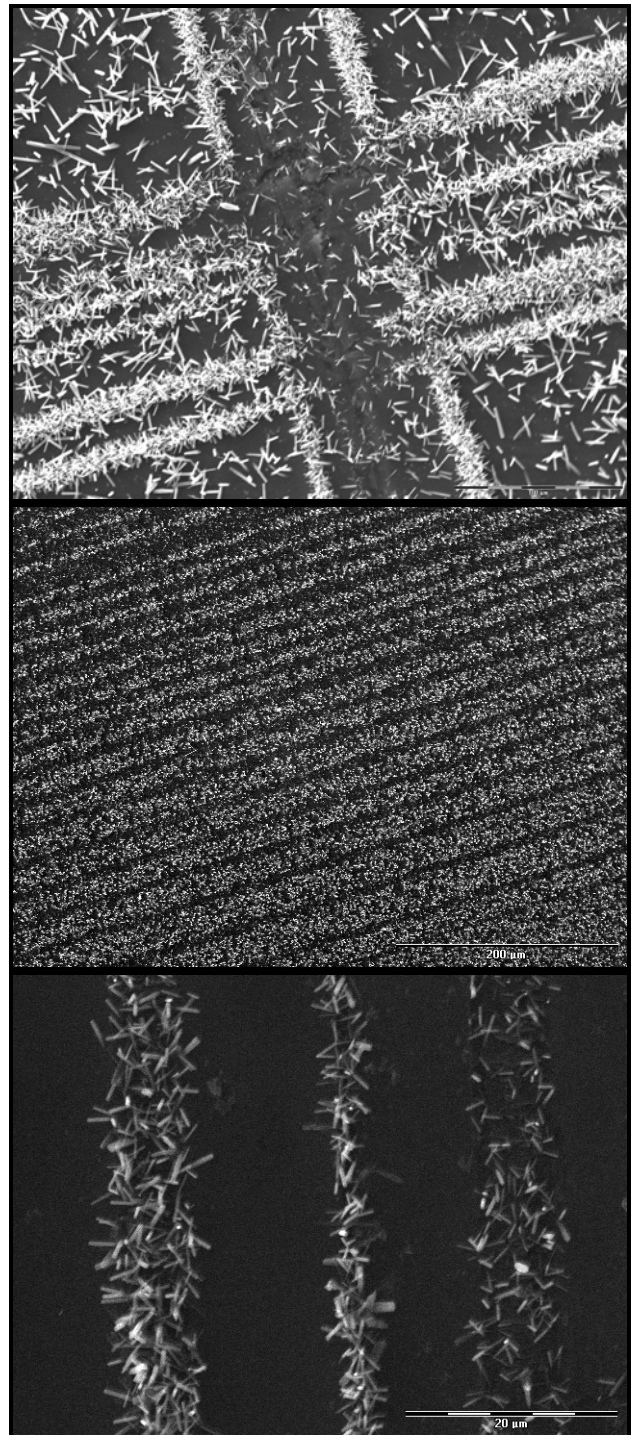


Fig. 2) SEM micrographs of patterned 3-D arrays of crystalline ZnO on Si/SiO₂ wafer substrate by aqueous chemical growth.

References

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